

10. (Amended) A photosensitive resin composition for i-line stepper using monochromatic light, which comprises (1) a polyimide precursor, formed from an oxydiphthalic acid or acid anhydride thereof as a reactant, a 20 μ m film thickness of said polyimide precursor having a transmittance, at 365nm, of at least 40%; and (2) a polymerization initiator.

Please add the following new claims to the application:

-- 20. A photosensitive resin composition according to claim 10, wherein the composition further comprises an addition-polymerizable compound.

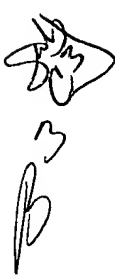
21. A photosensitive resin composition according to claim 20, wherein the addition-polymerizable compound is tetraethylene glycol dimethacrylate.

22. A photosensitive resin composition according to claim 10, wherein the polyimide precursor is formed from an oxydiphthalic acid or acid anhydride thereof with a diamine.

23. A photosensitive resin composition according to claim 22, wherein said diamine is a diaminodiphenyl ether.


24. A photosensitive resin composition according to claim 22, wherein the diamine is selected from the group consisting of 4,4'-diaminodiphenyl ether, 2,4'-diamino-

diphenyl ether, 3,4'-diaminodiphenyl ether and 3,3'-diaminodiphenyl ether.


 25. A photosensitive resin composition which comprises a polyimide precursor formed from an oxydiphthalic acid or acid anhydride thereof with a diamine, and which is adapted to be exposed and developed using an i-line stepper which uses monochromatic light.

26. A photosensitive resin composition according to claim 25, wherein the composition further includes a polymerization initiator.

27. A photosensitive resin composition according to claim 26, wherein the composition further comprises an addition-polymerizable compound.

 28. A photosensitive resin composition according to claim 27, wherein the addition-polymerizable compound is tetraethylene glycol dimethacrylate.

29. A photosensitive resin composition according to claim 28, wherein said diamine is a diaminodiphenyl ether.

 30. A photosensitive resin composition according to claim 27, wherein said diamine is a diaminodiphenyl ether.

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31. A photosensitive resin composition for i-line stepper using monochromatic light, which comprises a polyimide precursor, formed from an oxydiphthalic acid or acid anhydride thereof with a diamine.

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32. The photosensitive resin composition according to claim 31, wherein the composition further comprises a polymerization initiator.

33. The photosensitive resin composition according to claim 32, wherein the composition further comprises an addition-polymerizable compound.

34. The photosensitive resin composition according to claim 33, wherein the addition-polymerizable compound is tetraethylene glycol dimethacrylate.

35. A photosensitive resin composition according to claim 31, wherein said diamine is a diaminodiphenyl ether.

36. A photosensitive resin according to claim 31, wherein the diamine is selected from the group consisting of 4,4'-diaminodiphenyl ether, 2,4'-diaminodiphenyl ether, 3,4'-diaminodiphenyl ether and 3,3'-diaminodiphenyl ether. --